

## Ion Beam Sputter Target and Method of Manufacture

### **Disclosure Number**

201002398

### **Technology Summary**

The invention relates to a sputtering target for carrying out a Physical Vapor Deposition (PVD) coating process and more specifically, a PVD coating process where the sputtering target is sputtered by bombardment with gas atoms and/or ions and a layer consisting of a plurality of metallic elements is deposited on a substrate. The sputtering target is comprised of a plurality of target tiles made of a first chemical composition alternated in position with a plurality of target tiles made of a second chemical composition. In another embodiment, additional target tiles made of other chemical compositions can also be alternated in position with the first and second target tiles. In still another embodiment, tiles of a third chemical composition are stacked on top of the tiles made of the first or second chemical composition.

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